

Notice of References Cited	Application/Control No. 10/665,998	Applicant(s)/Patent Under Reexamination SCHAADT ET AL.	
	Examiner Eric B. Chen	Art Unit 1765	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-4,498,953	02-1985	Cook et al.	438/738
	C	US-6,436,229	08-2002	Tai et al.	257/E21.218
	D	US-6,558,559	05-2003	Becker et al.	216/2
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	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

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	U	Wolf et al., Silicon Processing for the VLSI Era, 1986, Lattice Press, Vol. 1, pp 386, 332-33, 399, 514, 520, 565-67.
	V	Wolf, Silicon Processing for the VLSI Era, 2002, Lattice Press, Vol. 4, pp. 66-67.
	W	Rossnagel et al., Handbook of Plasma Processing, 1990, Noyes Publications, pp. 200-01.
	X	Ashurst et al., Journal of Microelectromechanical Systems, March 2001, Vol. 10, No. 1, pp. 41-49.

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.